

Supplementary Information

**Combined Experimental-Theoretical Study of the
Optoelectronic Properties of Non-Stoichiometric Pyrochlore
Bismuth Titanate**

Dalal Noureldine,¹ Sheikha Lardhi,¹ Ahmed Ziani,¹ Moussab Harb,^{1*} Luigi Cavallo,¹ and Kazuhiro Takanabe^{1*}

Division of Physical Sciences and Engineering, KAUST Catalysis Center (KCC), King Abdullah University of Science and Technology (KAUST)

4700 KAUST, Thuwal, 23955-6900, Saudi Arabia

E-mail addresses: moussab.harb@kaust.edu.sa; kazuhiro.takanabe@kaust.edu.sa

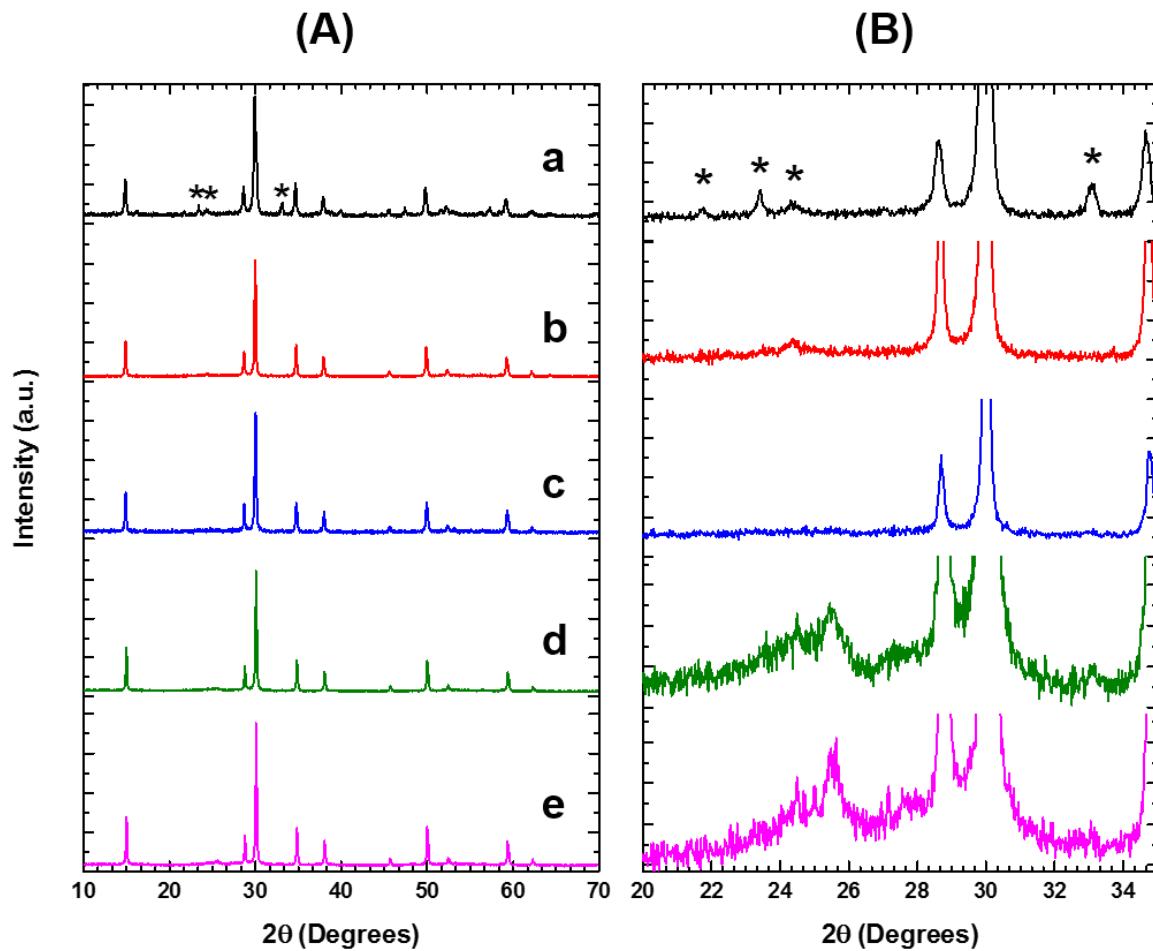


Fig. S1. A) XRD patterns of the powder samples prepared with different Ti/Bi ratio of (a) 1, b) 1.23, c) 1.50, d) 1.75, e) 2.00. B) The magnified XRD patterns where the amorphous phases and the $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ secondary phase (asterisk) are observed.

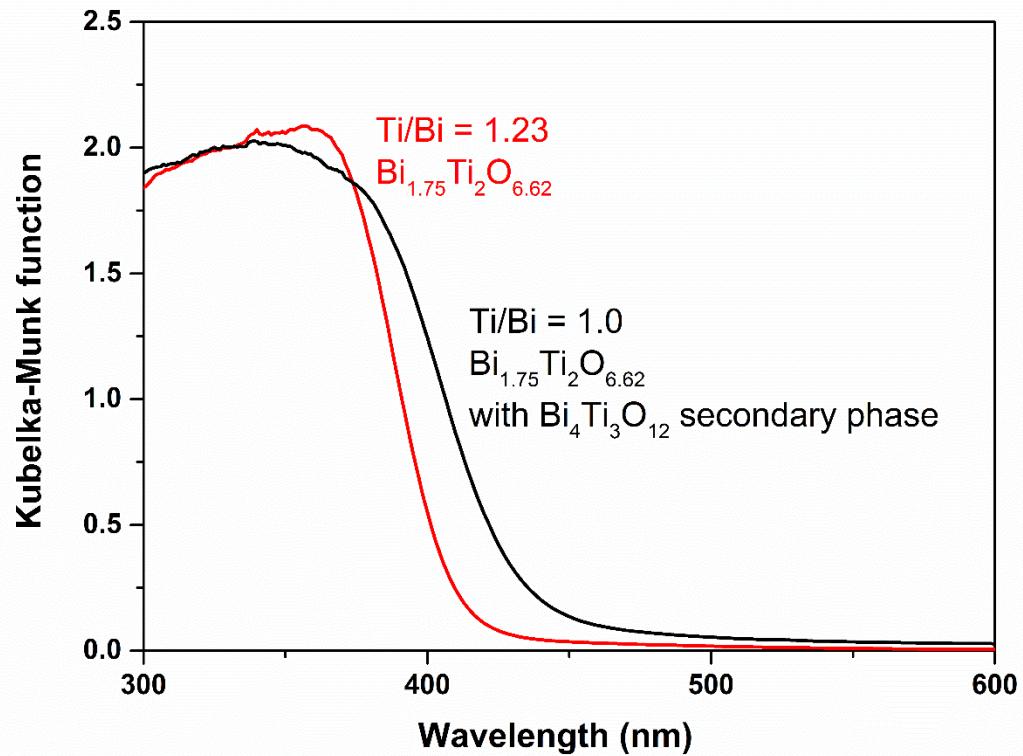


Fig. S2. Diffuse reflectance UV-Vis spectra of the powder sample with $\text{Ti}/\text{Bi} = 1.0$ containing $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ secondary phase and the sample with $\text{Ti}/\text{Bi} = 1.23$ (single phase).

Table S1. Rietveld atomic positions and occupancy for bismuth, titanium, and oxygen atoms in $\text{Bi}_{1.75}\text{Ti}_2\text{O}_{6.62}$ sample.

atom	Wyckoff position	x	y	z	occupancy
Bi	96	0.00000	-0.02846	0.02846	0.1463
Ti	16	0.50000	0.50000	0.50000	1
O	48	0.12500	0.12500	0.43297	1
O'	8	0.12500	0.12500	0.12500	0.624

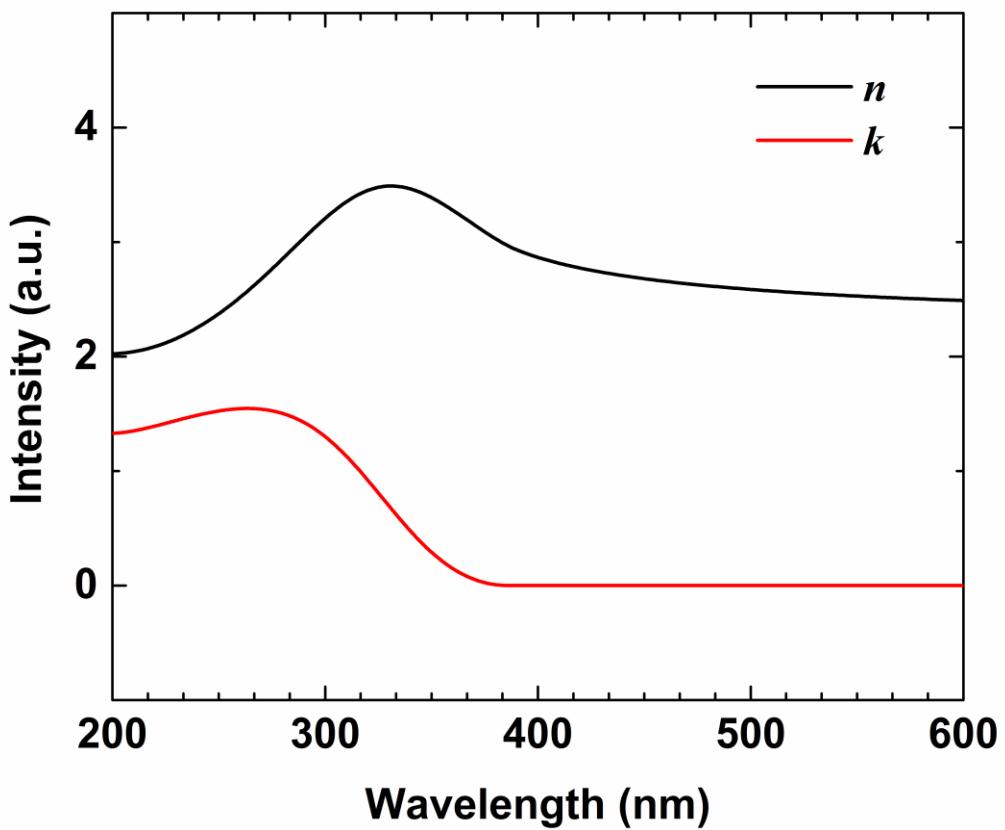


Fig. S3. Refractive index components measured by spectroscopic ellipsometry for $\text{Bi}_{1.75}\text{Ti}_2\text{O}_{6.62}/\text{Si}$ film.

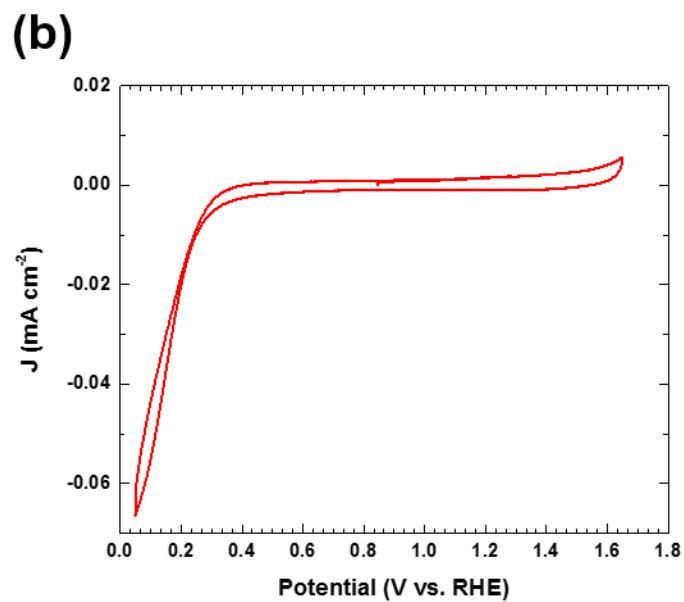
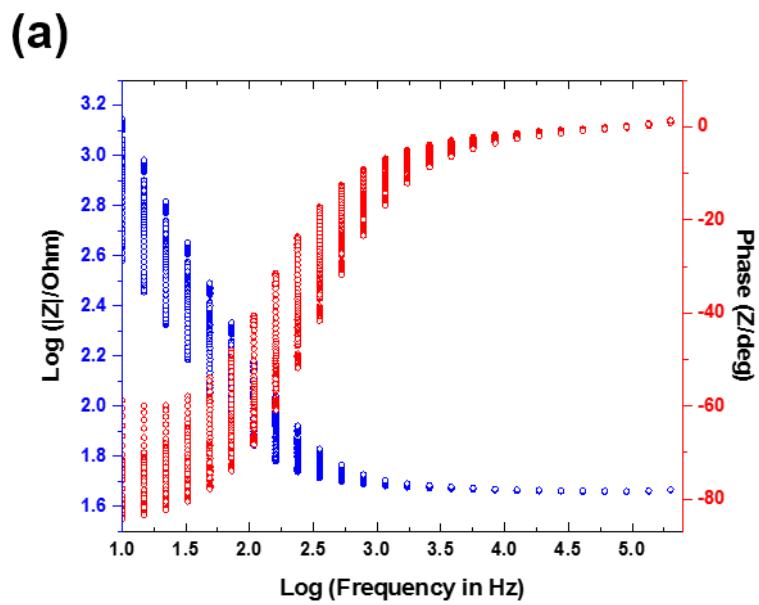


Fig. S4. a) Cyclic voltammetry Bi_{1.75}Ti₂O_{6.62}/FTO film measured in 0.1 M NaOH solution, pH 13, b) the XRD of the Bi_{1.75}Ti₂O_{6.62}/FTO film used for Mott-Schottky (stars correspond to peaks of FTO substrate).